TSMC-03-186

April 16, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: Serial No. 10/808,802 03/24/04

Fu-Kai Yang et al.

A TWO STEP TRENCH DEFINITION PROCEDURE FOR FORMATION OF A DUAL DAMASCENE OPENING IN A STACK OF INSULATOR LAYERS

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty of disclosure under CFR 1.97-1.99 and 37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on April 26, 2004.

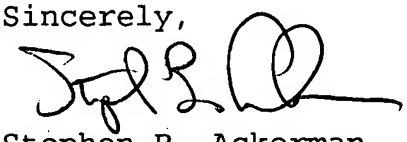
Stephen B. Ackerman, Reg.# 37761

Signature/Date SBA 4/26/04

U.S. Patent 6,211,035 to Moise et al., "Integrated Circuit and Method," discusses capacitor and memory structures and fabrication methods for such structures.

U.S. Patent 6,211,063 to Liu et al., "Method to Fabricate Self-Aligned Dual Damascene Structures," describes a method to form dual damascene structures.

Sincerely,



Stephen B. Ackerman,
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Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

APR 2 9 2004 PATENT & TRADEMARK OFFICE TC 2800

Docket Number (Optional)	Application Number
TSMC-03-186	10/808,802
Applicant: Fu-Kai Yang et al.	
Filing Date: 03/24/04	Group Art Unit:

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	6211035	4/3/01	Moise et al.	438	396	9/9/99
	6211063	4/3/01	Liu et al.	438	624	5/25/99

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation YES	Translation NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER	DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.